

<b>Session Title:</b>	<b>[TA2] Nanoscale Thin Film Deposition IV</b>
<b>Session Date:</b>	<b>November 15 (Tue.), 2022</b>
<b>Session Time:</b>	<b>11:20-12:20</b>
<b>Session Room:</b>	<b>Room A (Capri Room, 2F)</b>
<b>Session Chair:</b>	<b>Prof. Woongkyu Lee (Soongsil Univ., Korea)</b>

**[TA2-1]** 11:20-11:40

**Conformal Crystalline Ge-Sb-Te Thin Films for Phase Change Memory Applications**

Yewon Kim, Okhyeon Kim (Sejong Univ., Korea), Chang Yup Park, Dong Geon Koo, Dong-Ho Ahn, Bong Jin Kuh (Samsung Electronics Co., Ltd., Korea), and Won-Jun Lee (Sejong Univ., Korea)

**[TA2-2]** 11:40-12:00

**Insight into Atomic Layer Deposition and Chemical Vapor Deposition for Future Device Explorer**

Honggun Kim, Chungil Hyun, Hyungi Kim, Sangwoo Lee, Youngseop Rah, Changgu Jung, Kyoungcho Jang, Changwon Choi, Seongtae Oh, Youngwoo Park, and Jaihyung Won (Tokyo Electron Korea Ltd., Korea)

**[TA2-3]** 12:00-12:20

**Change of RPALD Titanium Oxide Film Properties by Applying Positive DC-Bias**

Junyoung An, Suhyeon Park, Heejun Yoon, Seokhwi Song (Hanyang Univ., Korea), Wonbong Cho, Pashupati Adhikar (Univ. of North Texas, USA), and Hyeongtag Jeon (Hanyang Univ., Korea)